

A Self-Aligned InGaAs HEMT Architecture for Logic Applications

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Abstract—In this paper, we present a novel self-aligned process for future III–V logic FETs. Using this process, we have demonstrated enhancement-mode 90-nm-gate-length InGaAs HEMTs with excellent logic figures of merit. We have carried out a detailed analysis of this device architecture to determine its future scaling capabilities. We find that, as the insulator is scaled to achieve enhancement mode, the performance of the device is limited by degradation of the I_{ON}/I_{OFF} ratio due to gate leakage current. By use of TLM test structures, we have determined that the barrier resistance dominates the source resistance. We use a tri-layer TLM model to predict the expected evolution of the contact resistance as it is scaled to realistic VLSI dimensions and find that the current technology results in resistance values that are two orders of magnitude higher than the desired target for sub-22-nm nodes. Using the model, we explore different options for device redesign. Both I_{ON}/I_{OFF} and source-resistance limitations imply that the use of a high- k gate dielectric will be required for future device implementations.

Index Terms—Contact resistance, FET logic devices, HEMT.

I. INTRODUCTION

RECENT excellent results achieved by short-channel InGaAs HEMTs [1], [2] have demonstrated the potential for using III–V as a channel material in future CMOS generations. To date, InGaAs HEMTs have typically been used for fiber-optic front-end systems and millimeter-wave applications where the device footprint is not of utmost concern. However, reduction of device pitch is the main driving force for logic processes. The 2007 ITRS roadmap calls for a metal-1 device half pitch of 15 nm for high-volume microprocessors by 2020 [3]. In contrast to this, state-of-the-art HEMTs typically have a source–drain separation on the order of 1.5–2 μm . Therefore, in order to fulfill the promise of III–V-based FETs, a self-aligned architecture that allows a VLSI device pitch to be achieved must be implemented.

The most obvious approach to self-alignment, i.e., that of self-aligning source and drain implants to a refractory gate, has been used in the fabrication of AlGaAs/GaAs-based HEMTs [4], [5]. However, in the case of InAlAs/InGaAs-based devices,

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which are preferable because of their higher channel mobility, the low dopant activation levels achieved in the source/drain regions limit the usefulness of this approach. The most typical self-alignment technique for the InAlAs/InGaAs system is to use the head of a T-gate as a shadow mask for source/drain metal deposition [6]. Excellent results have been achieved with 50-nm devices using this approach, but as the degree of self-alignment is determined by the size of the gate head, the source/drain spacing is still 0.3 μm [7]. The fringing capacitance introduced by the overlap of the T-gate with the source/drain regions also poses a disadvantage, and as this approach requires the use of a T-gate, it is not suited for VLSI.

In this paper, which is an updated and expanded version of an earlier presentation [8], we present a novel self-aligned architecture for InGaAs-based HEMTs. We have demonstrated an ohmic-gate separation of less than 30 nm, which is $> 30\times$ improvement over that of conventional device designs. We employ a nonalloyed ohmic contact scheme, which is a key requirement for VLSI applications. To achieve enhancement-mode devices (another key requirement for logic applications), we have vertically scaled the barrier/insulator thickness (t_{ins}) by means of a dry etch. We demonstrate 90-nm-gate-length enhancement-mode self-aligned devices with excellent logic figures of merit.

We use the results of devices to examine the potential of further scaling this device architecture. We find that as the device becomes enhancement mode, the $I_{\text{on}}/I_{\text{off}}$ ratio seriously degrades. A detailed study of the source resistance (R_s) through TLM test structures reveals that the resistance associated with the barrier layer in the extrinsic device limits R_s . By applying a trilevel TLM model to the source, we find that, as the device is scaled to true VLSI dimensions, R_s increases dramatically if the current cap design is maintained. We use this model to investigate alternative approaches to the source design and suggest that, by eliminating the barrier and grading the cap to pure InAs, an acceptable contact resistance could be achieved.

II. DEVICE FABRICATION

The main aim of this paper is the development and implementation of a self-aligned HEMT architecture that is suited for VLSI applications. Based on the analysis of conventional HEMTs and considerations of previous efforts at self-alignment, as discussed in the Introduction, certain elements were determined to be of key importance to the design. These are as follows.

- 1) Nonalloyed ohmic contacts must be used to avoid reliability issues, to have a planar surface, and to achieve

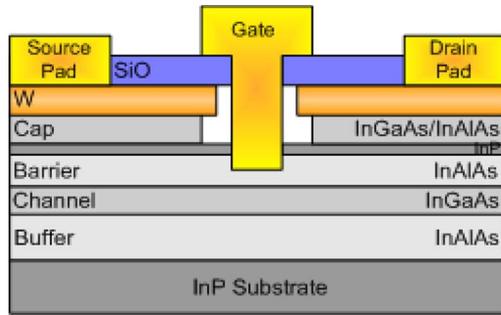


Fig. 1. Schematic cross section of the self-aligned device concept. W source/drain metallizations are separated from the gate by means of an air spacer.

the edge definition required for a very tight ohmic-gate spacing.

- 2) The use of the cap structure should be maintained in order to achieve the minimum possible value for the source and drain resistances.
- 3) The method of self-alignment should not be dependent on the physical structure of the gate. That is, the ohmic-gate separation should easily be varied, irrespective of the gate length or gate-head size.
- 4) The process should be well controlled to enable spacers in the few tens of nanometer range.
- 5) The devices fabricated should be of deep-submicrometer gate lengths to ensure that issues of relevance for future devices are studied.

Using the design space defined by these requirements, the self-aligned device architecture shown in Fig. 1 was conceived and implemented. The key feature of the structure is that a nonalloyed tungsten (W) source/drain metal is self-aligned to the gate by means of an “air spacer.” The self-alignment is achieved by means of a two-step e-beam lithography process. In the first step, the gate foot is defined by etching a SiO overlayer and the W layer. At this point, W is coincident with the edge of the SiO layer. The air spacer is formed by pulling back W from the edge of the SiO layer by means of a highly selective isotropic plasma etch. During the subsequent liftoff process defined by the second lithography step, the deposited gate metal ends up being aligned to the edge of the SiO layer at a distance that is set by the W pull-back etch.

A description of the heterostructure used for device fabrication in this paper is given in [9]. The process flow (Fig. 2) begins with the deposition of 60 nm of tungsten that forms the source/drain ohmic metallization. Tungsten is RF sputter deposited in a homemade Advanced Engineering-based sputter system at a rate of 1 Å/s. Prior to deposition, the substrate is cleaned in a dilute 5% NH_4OH solution. Following W deposition, a 70-nm SiO layer is deposited by the PECVD system at 300 °C [Fig. 2(b)]. The contact resistance of W to the heavily doped cap was found to vary very little up to temperatures of 600 °C when annealed by RTA. The value of the W contact resistance measured by TLM test structures of $60 \Omega \cdot \mu\text{m}$ is consistent with those obtained in [10]. The thermal stability of the contact resistance is the hallmark of an effective nonalloyed ohmic contact scheme, as alloyed contacts in InP-based HEMTs

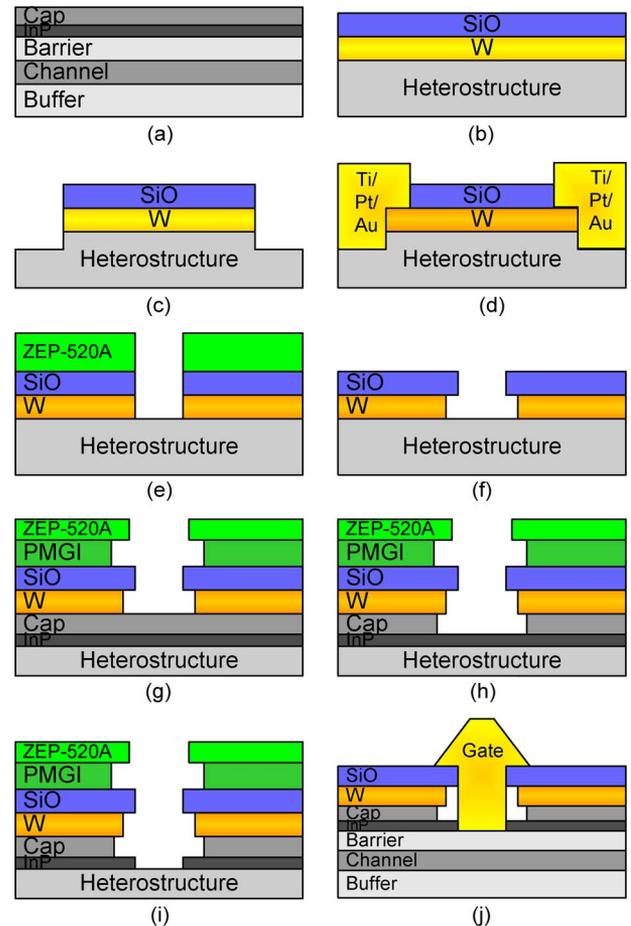


Fig. 2. Self-aligned HEMT process flow [(e) and onward show a zoomed-in version of (a)–(d)]. (a) Starting heterostructure. (b) W and SiO deposition. (c) Mesa isolation. (d) Source/drain pad deposition. (e) First e-beam lithography and W/SiO etch for gate-foot definition. (f) Spacer etch to pull W back from the edge of SiO. (g) Second e-beam lithography; a double-development procedure is used to create an overhang profile for liftoff. (h) Recess etch; the cap is etched under W. (i) Ar RIE etch to remove the InP etch stopper. (j) Gate metal deposition and liftoff.

are very sensitive to temperature and usually severely degrade at temperatures above 400 °C [11].

Device isolation in this process flow is achieved by means of mesa etching [Fig. 2(c)]. The SiO and W layers are both dry etched, and the underlying heterostructure is then wet etched. At this point, contact pads are deposited on W [Fig. 2(d)]. The pads are defined using an image reversal resist, which results in a 2- μm source/drain pad spacing. The SiO layer covering the W is removed with the same CF_4 dry etch as that used in mesa etching. The resist is still intact after this etch and is used for the liftoff of Ti/Pt/Au (25 nm/25 nm/300 nm) deposited by e-beam evaporation.

The gate of the device is formed by a two-step e-beam lithography process [Fig. 2(e)–(j)]. The first step defines the gate foot in the SiO/W layer and thus determines the gate length [Fig. 2(e)]. The spacer is also formed at this point ultimately, resulting in a self-aligned structure [Fig. 2(f)]. The second step defines the gate head and is used for the liftoff of the gate metal [Fig. 2(g)]. We use a T-gate process here to ensure the mechanical stability of the gate as it runs over the step formed by mesa isolation. In a planar isolation process such as STI, our

gate fabrication can be performed in a single lithography step, resulting in a trapezoidal, rather than a T-gate, shape. In this case, the oxide may also be removed to reduce the gate fringing capacitance.

The first step of the gate formation process involves gate-foot definition in the SiO/W bilayer system [Fig. 2(e)]. A high-resolution process is required to achieve short gate lengths. To this end, a 500-nm layer of ZEP-520A resist from Nippon Zeon Corporation was used. ZEP-520A offers a large etch resistance, as well as high resolution, and has been used to define gate lengths as short as 30 nm [12]. The gate-foot pattern is written in the ZEP layer by means of a Raith-150 e-beam lithography tool at an energy of 30 keV and a dose of $1700 \mu\text{C}/\text{cm}^2$. The SiO and W layers are dry etched using CF_4/He and SF_6/O_2 chemistries, respectively. The W etch was adapted from the work of Pearton *et al.* [13], with the dc bias being set at -50 V to avoid plasma-induced damage in the semiconductor. At this point, W is coincident with the edge of the SiO layer [Fig. 2(e)]. A lateral plasma O_2/CF_4 -based etch is now performed, which selectively pulls W back from the SiO edge, thus creating an “air spacer” [Fig. 2(f)]. This spacer etch is the key enabling step of the process. The lateral etch rate of W is well controlled at about 0.2 nm/s and can thus be timed to set the desired distance to the gate. The selectivity of the etch to the SiO layer and heterostructure was measured within our metrology capabilities to be $>100:1$. The gate metal will subsequently be deposited and fill the opening defined by the SiO layer. Therefore, W that forms the source/drain metallization becomes self-aligned to the gate.

The spacer etch is followed by the second e-beam lithography step that is used for gate liftoff. The substrate is coated with a bilayer of resist that consists of $1\text{-}\mu\text{m}$ PMGI and a 200-nm-layer of 1:1 ZEP-520A:anisole. The gate head is aligned back to the previously etched gate-foot pattern and is exposed at 30 keV with a dose of $50 \mu\text{C}/\text{cm}^2$. A double-development process is used to create an overhang profile that is suitable for liftoff [Fig. 2(g)]. ZEP-520A is developed with a 2:3 mixture of MEK:MIBK. The PMGI is then wet etched using the CD-26 developer that undercuts ZEP-520A. This second lithography step could be omitted if a trapezoidal-shaped gate is desired and a thicker ZEP-520A layer is used in the first step to define both gate-foot and liftoff patterns.

Gate-recess etching is performed following a two-step recess approach originally proposed by Suemitsu [14]. The cap layers of InGaAs and InAlAs are wet etched with a 20:1 citric acid: H_2O_2 mixture that selectively stops on the InP layer [Fig. 2(h)]. The cap is overetched so that there is sufficient lateral distance between the cap and the gate. From previous experience in fabricating devices on this heterostructure, the lateral etching distance (L_{side}) is targeted to be 150 nm [15] to strike the best balance between performance and short-channel effects. The actual devices had an L_{side} of 200 nm. In a future optimized heterostructure, this distance should optimally be designed to be identical to the ohmic-gate spacing.

Following this, the InP etch stopper is removed using an Ar-based RIE step [Fig. 2(i)]. This Ar etch was reported by Suemitsu [16] to be somewhat selective to the InAlAs insulator layer with a selectivity on the order of 17:1. We have found

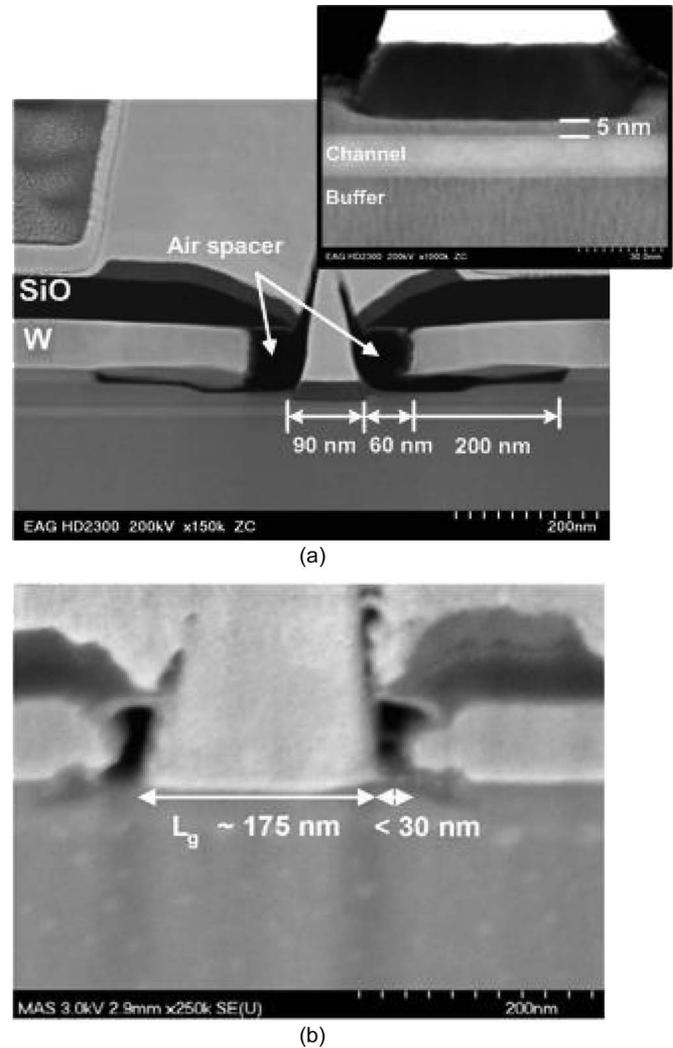


Fig. 3. (a) TEM of a completed 90-nm self-aligned device. The gate-to-source-ohmic metal distance is 60 nm. L_{side} is estimated to be 200 nm. Device optimization could reduce the need for such a large L_{side} . The inset shows that the barrier thickness has been thinned to 5 nm. (b) Cross-sectional SEM of a completed self-aligned 175-nm device where the ohmic-gate spacing is less than 30 nm. (This device is operational, but its characteristics are not reported in this paper.)

this etch to be not as selective, and by increasing the etching time, the InAlAs barrier layer could be thinned in a controlled manner. In this paper, we have fabricated devices with gate-to-channel distances of 11 and 5 nm. A feature of this process is that the Ar dry etch only thins the insulator layer directly under the gate, thus preserving the access resistance.

The device is completed by the deposition and liftoff of a Ti/Pt/Au (25 nm/25nm/600 nm) metal stack [Fig. 2(j)]. This thick stack provides adequate step coverage of the gate metal over the mesa edge.

Using the described process, we have fabricated devices with gate lengths between 90 and 240 nm. A cross-sectional TEM of a self-aligned 90-nm device is shown in Fig. 3(a). The InAlAs insulator layer of this device was thinned by the Ar RIE etch and has a gate-to-channel distance of 5 nm. We also fabricated devices with a nominal barrier thickness (t_{ins}) of 11 nm. The ohmic-gate separation is about 60 nm. In a separate run, we succeeded in fabricating functional longer channel devices in

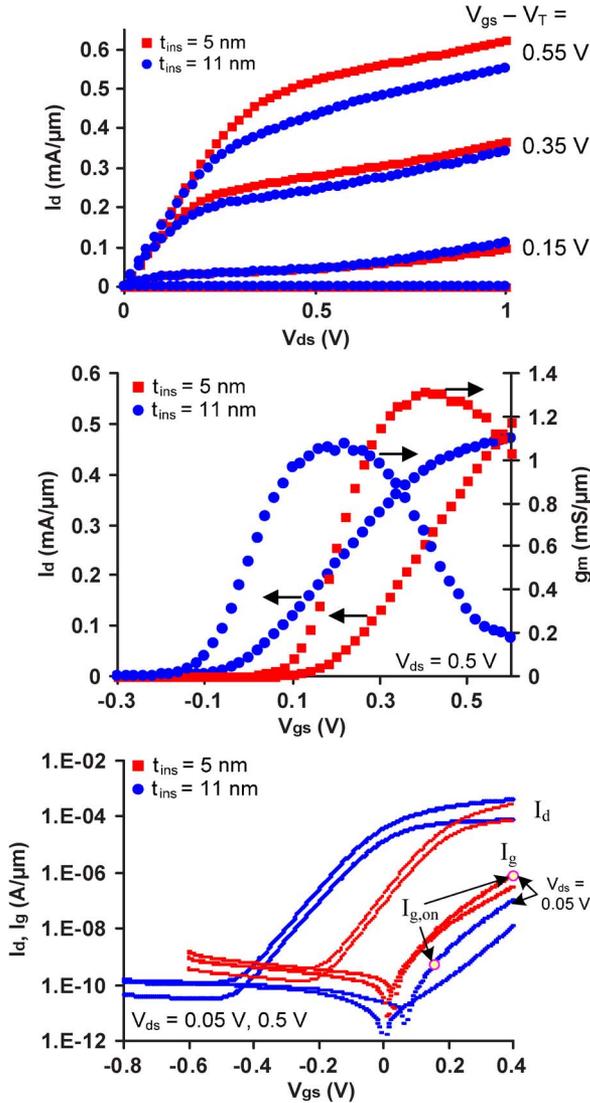


Fig. 4. Output, transfer, and subthreshold characteristics of 90-nm-gate-length devices with $t_{\text{ins}} = 11$ - and 5-nm devices. The device performance improves as the insulator is scaled. The $I_{g,\text{ON}}$ point (shown in the $V_{\text{ds}} = 0.05$ -V curve to estimate the gate-ON-drain-OFF condition) of the enhancement-mode 5-nm- t_{ins} device is further along the exponential gate leakage current curve, resulting in a reduced $I_{\text{ON}}/I_{\text{LEAK}}$ ratio.

which the spacer distance was as small as 30 nm [Fig. 3(b)]. This is an improvement of $> 30\times$ over conventional designs.

III. RESULTS AND DISCUSSION

A. DC Characteristics

Both sets of devices with t_{ins} 's of 5 and 11 nm demonstrated excellent dc characteristics. These are shown in Fig. 4 for devices of 90-nm gate length. The thin-barrier devices are in enhancement mode with a V_T of 60 mV (defined at $1 \mu\text{A}/\mu\text{m}$) for 90-nm gate length, a peak transconductance (g_m) of $1.32 \text{ mS}/\mu\text{m}$, and drain-induced barrier lowering (DIBL) and subthreshold swing (SS) of 55 mV/V and 70 mV/dec, respectively. This represents a positive shift in V_T of 0.2 V over the 11-nm- t_{ins} device and a significant increase in peak g_m from $1.07 \text{ mS}/\mu\text{m}$ for the 11-nm- t_{ins} device. The DIBL and SS val-

ues for $t_{\text{ins}} = 11 \text{ nm}$ are also worse at 88 mV/V and 80 mV/dec, respectively. A tradeoff of barrier scaling is the increase in gate current of the 5-nm- t_{ins} device due to enhanced tunneling.

The scaling behavior of the two sets of devices is shown in Fig. 5. The g_m of the 11-nm- t_{ins} devices peaks at an L_g of 145 nm and then begins to decrease, which is consistent with the observations of Shinohara *et al.* [17]. g_m continues to scale to at least 90 nm for the 5-nm- t_{ins} samples [Fig. 5(a)]. V_T roll-off is much suppressed in thinner insulator samples with a decrease in V_T of 52 mV for $t_{\text{ins}} = 5 \text{ nm}$ compared to 132 mV for $t_{\text{ins}} = 11 \text{ nm}$ as the device gate length scales from 220 to 90 nm [Fig. 5(b)]. DIBL and SS also improve as t_{ins} is decreased. All these figures of merit are defined as in [18]. The short-channel figures of merit achieved by $t_{\text{ins}} = 5$ -nm devices are excellent and at least comparable to the best published data on Si CMOS devices from the literature of similar gate length [Fig. 5(c)]. These results demonstrate the merits of the dry-etch approach and the benefits that are achievable from vertical scaling.

We have also compared these devices in terms of their $I_{\text{ON}}/I_{\text{OFF}}$ ratio. In III-V FETs, it is important to include the gate leakage current in the OFF current. We denote this combined current by I_{LEAK} [19]. We define I_{LEAK} to be the average of the current through the device in the two cases when the following are observed: 1) The gate is OFF and the drain ON (I_{OFF}), and 2) the gate is ON and the drain OFF ($I_{g,\text{ON}}$)

$$I_{\text{LEAK}} = \frac{1}{2}(I_{\text{OFF}} + I_{g,\text{ON}}). \quad (1)$$

As in [20], I_{OFF} is defined at $V_{\text{gs}} = V_T - 1/3V_{\text{dd}}$ ($V_{\text{dd}} = 0.5 \text{ V}$), and $I_{g,\text{ON}}$ and I_{ON} are defined at $V_{\text{gs}} = V_T + 2/3V_{\text{dd}}$, with $V_{\text{dd}} = 0.5$ and 0.05 V , respectively. The $I_{\text{ON}}/I_{\text{LEAK}}$ ratios for the 5- and 11-nm- t_{ins} devices are then 1.8×10^3 and 6.3×10^4 , respectively. The 5-nm- t_{ins} device is in enhancement mode, and at $V_{\text{gs}} = V_T + 2/3V_{\text{dd}}$, the gate is strongly forward biased. I_g increases exponentially in the forward-bias regime, resulting in a significantly higher value of $I_{g,\text{ON}}$ for the 5-nm- t_{ins} device compared to that for the 11-nm- t_{ins} device (Fig. 4). This decrease in $I_{\text{ON}}/I_{\text{LEAK}}$ ratio is a tradeoff that has to be taken into consideration when thinning the insulator to achieve enhancement-mode devices. Development of a gate-dielectric technology for III-V quantum-well MOSFET implementations is expected in the long run to address these gate leakage issues.

B. Source Resistance

The source resistance (R_s) was measured directly from devices using the gate-current injection method [21], resulting in values of 220 and 235 $\Omega \cdot \mu\text{m}$ for the $t_{\text{ins}} = 11$ - and 5-nm samples, respectively. The relatively small change in R_s as the barrier is thinned is in contrast to the results obtained by Kim and del Alamo [22], where R_s increased as the barrier was thinned by means of a wet-etch process. We attribute the better R_s results achieved in this paper to the fact that the dry etch used to thin the barrier is anisotropic in nature.

To further understand the constituent components of R_s , we adopt a simple model of the source resistance for our devices, as shown in Fig. 6, along with an estimate for their values, as

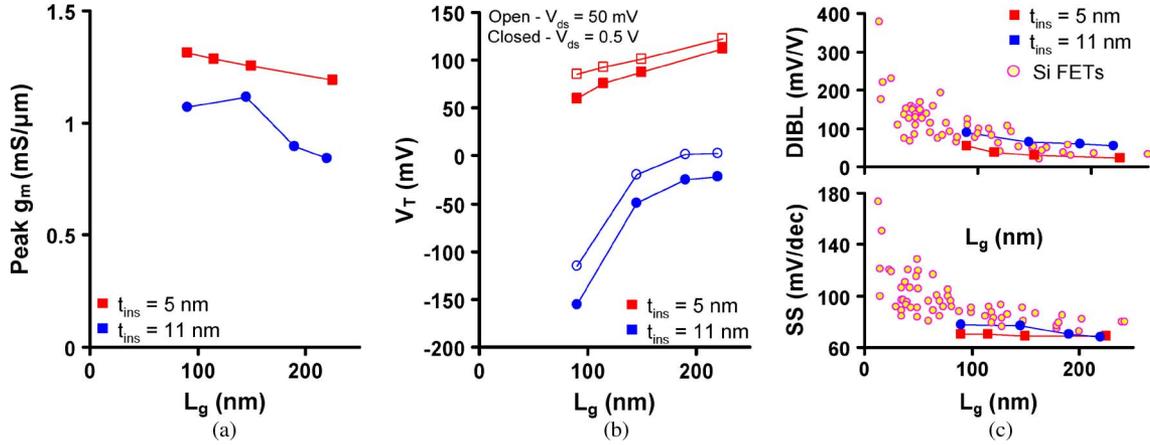


Fig. 5. Scaling behavior for the self-aligned devices with $t_{\text{ins}} = 11$ and 5 nm. Thinning of the insulator results in an improvement in DIBL, SS, and V_T roll-off. The $t_{\text{ins}} = 5$ -nm devices show outstanding short-channel effects when compared to Si CMOS devices.

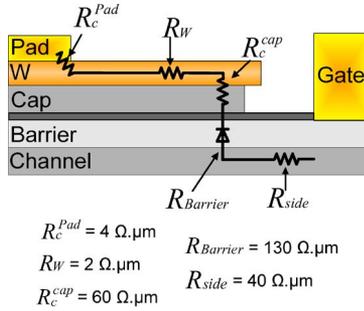


Fig. 6. Schematic of the component elements of the source resistance in the self-aligned device (with a nominal t_{ins} of 11 nm) and their extracted values from TLM measurements. As the contacts are nonalloyed, the current must flow from the contact through the heterobarrier and then into the channel. Based on a 1- μm spacing between the gate and the source pad and 200-nm L_{side} , the total R_s is estimated to be 230 $\Omega \cdot \mu\text{m}$ from TLM measurements.

determined from the TLM measurements described in [8]. The sum of these components results in an estimated R_s of 230 $\Omega \cdot \mu\text{m}$, which is consistent with the measured R_s values.

From this analysis, we find that R_{Barrier} is the dominant component of R_s (Fig. 6), accounting for more than 50% of the total value. R_c^{cap} is the next biggest component comprising 27%. As would be expected from a self-aligned design, the resistances of the W layer (R_W) and the pad contact (R_c^{pad}) are negligible. Known methods to reduce the barrier resistance, such as using a double-delta-doping layer in the barrier [23] or further engineering of the cap layers [24], should result in further reductions in R_s .

C. Source-Resistance Scaling

In the analysis of devices and TLMs that was carried out previously, we assumed a semi-infinite contact length ($\sim 10 \mu\text{m}$). For typical power and microwave applications of HEMTs, this is a valid assumption. However, for a III-V FET device to be used in a VLSI environment, this is not the case. If we assume that the maximum allowable contact length (L_c) is the device half pitch that is less half the gate length, then, for the 15-nm node, a maximum available L_c of only about 10 nm must be assumed [3]. In the following, we project the value of

series resistance that is to be expected at these realistic contact dimensions.

To estimate how the R_s of self-aligned devices will scale as extrinsic device dimensions shrink, we must use a more sophisticated model for R_s than the simple lumped case previously discussed. To this end, we use a modified version of the distributed trilayer TLM model previously proposed by Reeves [25] (Fig. 7). Our structure technically comprises four layers—the extrinsic channel, the barrier, the cap, and the W metal. We can reduce it to the trilayer case by assuming that the first-order current conduction through the barrier layer is purely vertical. This is a good assumption because this is the highest resistive layer in our structure. The specific tunneling resistance from the extrinsic channel to the cap (ρ_t) is then treated as a contact resistance between the two layers, with W being the third layer. We also assume that the sheet resistance of W (measured at 2 Ω/sq) can be considered negligible. The key parameters required for the analysis are the sheet resistance of the cap layer (R_{Scap}) and the extrinsic channel region under the cap (R_{Sext}), ρ_t , the specific contact resistance between the cap and W (ρ_c), and the contact length L_c . In the work of Reeves, the R_c of the structure is expressed as

$$R_c = K \cdot \left(\frac{f(R_{\text{sext}} - \rho_t a^2) - (1-f)R_{\text{scap}}}{b \tanh(bL_c)} - \frac{f(R_{\text{sext}} - \rho_t b^2) - (1-f)R_{\text{scap}}}{a \tanh(aL_c)} \right) \quad (2)$$

where

$$K = R_{\text{sext}} / [\rho_t \cdot w \cdot (b^2 - a^2)] \quad (2.a)$$

$$a = \sqrt{\left[\left\{ c - (c^2 - 4R_{\text{sext}}R_{\text{scap}}/(\rho_t\rho_c))^{\frac{1}{2}} \right\} / 2 \right]} \quad (2.b)$$

$$b = \sqrt{\left[\left\{ c + (c^2 - 4R_{\text{sext}}R_{\text{scap}}/(\rho_t\rho_c))^{\frac{1}{2}} \right\} / 2 \right]} \quad (2.c)$$

$$c = [(R_{\text{scap}} + R_{\text{sext}})/\rho_t + R_{\text{sext}}/\rho_c] \quad (2.d)$$

and w is the device width.

It should be noted that the resistance value in (2) contains only a portion of the source directly under the contact and does not include the R_{Side} portion of R_s .

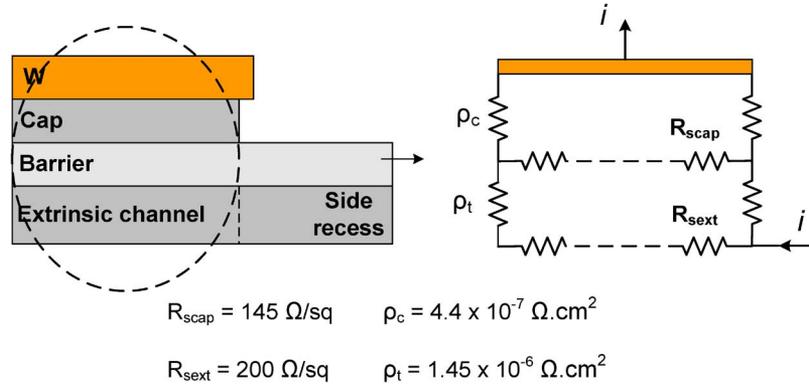


Fig. 7. Cross section of the nonalloyed ohmic contact and its corresponding trilayer TLM electrical network representation. We assume that current conduction in the barrier layer is only in the vertical direction and that the associated specific tunneling resistance ρ_t approximates a contact resistance between the extrinsic channel and cap layers. In this way, the nonalloyed contact reduces to a trilayer structure where all the current enters the contact through the extrinsic channel layer ($f = 1$ [13]).

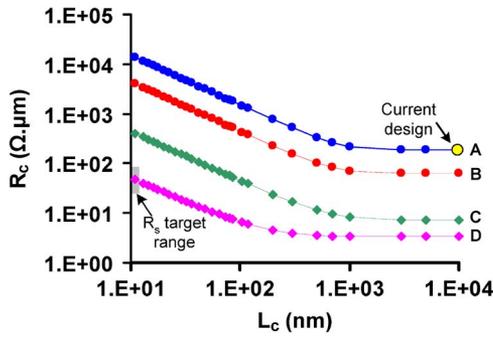


Fig. 8. Effect of contact-length scaling on R_c , as predicted by the use of trilayer approximation. (A) Current design. (B) Assumes that the barrier layer can be eliminated by use of a high- k dielectric solution, i.e., $\rho_t \rightarrow 0$. (C) Indium contact layer is increased to 70%. $R_{scap} \rightarrow 14 \Omega/\text{sq}$ and $\rho_c \rightarrow 4.4 \times 10^{-8} \Omega \cdot \text{cm}^2$. (D) Cap is graded to InAs ($\rho_c \rightarrow 5 \times 10^{-9} \Omega \cdot \text{cm}^2$).

The original analysis by Reeves considered an alloyed contact where current would enter the contact either through the alloyed layer sidewall or directly under the contact via R_{Sext} . The fraction of the current that enters in a conventional TLM manner through R_{Sext} is defined as f in (2). In the case of a nonalloyed ohmic contact, all the current enters the contact through R_{Sext} and $f = 1$. This results in simplification of (2) to

$$R_c = \frac{R_{sext}}{w \cdot \rho_t (b^2 - a^2)} \left(\frac{R_{sext} - \rho_t a^2}{b \tanh(bL_c)} - \frac{R_{sext} - \rho_t b^2}{a \tanh(aL_c)} \right). \quad (3)$$

R_{Scap} and ρ_c can be estimated directly from TLM test structures giving values of $145 \Omega/\text{sq}$ and $4.4 \times 10^{-7} \Omega \cdot \text{cm}^2$, respectively. The sheet resistance of the extrinsic channel under the cap (R_{Sext}) is different from that of R_{Side} , and we estimate it, by using a calibrated 1-D simulation of the heterostructure using nextnano, a self-consistent Schrödinger–Poisson solver [26]. This gives a value for R_{ext} of $200 \Omega/\text{sq}$. A value for ρ_t of $1.45 \times 10^{-6} \Omega \cdot \text{cm}^2$ is estimated by forcing the modeled R_c to match the measured one from the TLM structures.

Using these values, we use the model to predict the expected evolution of R_c as L_c is scaled to more realistic values (Fig. 8). From the 2007 ITRS roadmap, the maximum allowable parasitic source-plus-drain resistance (R_{sd}) at the 15-nm node is

145 or $72.5 \Omega \cdot \mu\text{m}$ for R_s . This $72.5\text{-}\Omega \cdot \mu\text{m}$ value could be considered an upper bound for the required R_s . For a lower bound, we require that the extrinsic device resistance results in no more than 20% decrease in I_{on} . To estimate the R_s needed to meet this requirement, we use the model of Antoniadis [27], where the width-normalized transistor current in saturation is defined as

$$I_D/W = C'_{inv} (V_{GS} - V_T) v \quad (4)$$

where C'_{inv} is the gate capacitance per unit area and v is the “effective” carrier velocity that can be expressed in terms of the virtual-source velocity (v_{x0}), source resistance (R_s), DIBL (δ), and C'_{inv} as

$$v = \frac{v_{x0}}{[1 + C'_{inv} R_s W (1 + 2\delta) v_{x0}]}. \quad (5)$$

Assuming an aggressive estimate for v_{x0} of 2×10^7 cm/s, C'_{inv} of 3×10^{-6} F/cm corresponding to an effective oxide thickness (EOT) of about 1 nm, and DIBL of 100 mV/V, R_s should not exceed $35 \Omega \cdot \mu\text{m}$ to limit the degradation of effective velocity (v) (and, thus, I_{on}) to less than 20%.

It is obvious from Fig. 8 curve A that, for our current technology, as L_c is scaled to 10 nm, R_c blows up and is over two orders of magnitude higher than the desired target range.

We have also used the model to evaluate different scenarios to obtain the desired contact resistance. We found that just changing R_{Scap} and ρ_c has very little impact on R_c as the barrier resistance represented by ρ_t dominates. We find that the only way to meet the desired target is to eliminate the barrier altogether. This implies the use of high- k -based gate-dielectric solution. Eliminating the barrier has the effect of reducing R_c by about a factor of three, but it is still far away from the target region (line B in Fig. 8). Next, we assume the use of a cap with 70% InAs composition. This should theoretically pull the Fermi level into the conduction band, thus resulting in a very low sheet resistance and a nearly ideal ohmic contact. Shinohara *et al.* [28] have reported an R_{Sheet} of $7 \Omega/\text{sq}$ using such a layer (about a factor-of-ten improvement over our design), and we similarly estimate a factor-of-ten reduction in ρ_c .

Again, a significant but not large-enough improvement in R_c is predicted (line C in Fig. 8).

Crook *et al.* [29] recently demonstrated a ρ_c of less than $1 \times 10^{-8} \Omega \cdot \text{cm}^2$ by using a highly doped ($3.5 \times 10^{19} \text{cm}^{-3}$) $\text{In}_{0.53}\text{Ga}_{0.47}\text{As}$ cap and paying close attention to the surface preparation before contact formation. However, the lowest demonstrated value of ρ_c has been by Nittono *et al.* [30], who achieved a value of $5 \times 10^{-9} \Omega \cdot \text{cm}^2$ by grading the contact layer to pure InAs. Grading the contact layer eliminates the internal potential barrier in the contact, thus reducing the contact resistance. This approach was originally for an HBT emitter, but such a cap design is possible in FETs. Assuming this demonstrated value of $5 \times 10^{-9} \Omega \cdot \text{cm}^2$ for the contact resistance, R_c is reduced to about $50 \Omega \cdot \mu\text{m}$ for an L_c of 10 nm (line D in Fig. 8), which falls within the target range. This analysis demonstrates that an aggressive approach to the extrinsic design of the device is needed to achieve the required performance of a future logic III–V FET with a self-aligned architecture.

IV. CONCLUSION

In conclusion, we have developed a self-aligned process that has allowed us to highlight the challenges and technical obstacles that need to be overcome in designing the extrinsic regions of future III–V devices. We have demonstrated 90-nm-gate-length InGaAs HEMTs with ohmic-gate–source separation of 60 nm, which is nearly a $20\times$ reduction over that of conventional architectures. We have also obtained devices in which this distance is as small as 30 nm. Using this process, we have fabricated enhancement-mode devices with an InAlAs barrier that was thinned to 5 nm by means of a dry etch. The dry etch did not degrade the device performance, and R_s did not increase significantly while yielding devices with excellent electrostatic integrity. Enhancement-mode devices of 90-nm gate length show outstanding logic characteristics in terms of current, g_m , and short-channel effects. We have examined the future scaling potential of devices and determined that, for the intrinsic device, the $I_{\text{on}}/I_{\text{off}}$ ratio as the insulator is thinned and, for the extrinsic device, the scaling of the source resistance with the contact length are the main limiting factors. Both issues can be addressed by introducing a high- k gate-dielectric insulator in the intrinsic gate stack.

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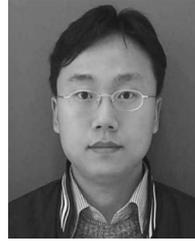
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